

Abstract Submitted
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Aluminum Nitride Thin Films for Pyroelectric Detection¹

NICHOLAS CALVANO, ANDREW VOSHELL, KEESEAN BRAITHWAITE, PHILIP CHROSTOSKI, Delaware State Univ, DENNIS PRATHER, University Of Delaware, MUKTI RANA, Delaware State Univ, DENNIS PRATHER COLLABORATION — A pyroelectric detector is a class of thermal detector for which there is a change in spontaneous polarization. Absorption of infrared radiation in the sensing layer of pyroelectric detector causes a change in temperature and hence changes in spontaneous polarization which finally generates a voltage. The objective of this work is to deposit and characterize thin films of Al_xN_y for using them as pyroelectric material. Capacitors of Al_xN_y thin films with Au electrodes were designed using Intellisuite software. Capacitors of various sizes were fabricated. The diameter of the electrodes for capacitor was varied between 400 μm to 1100 μm with 100 μm increment. The distances between two electrodes were varied between 400 μm to 1100 μm with 100 μm increment as well. On a 3 inch diameter cleaned quartz wafer, 20 nm thick Ti adhesion layer was deposited followed by a 100 nm thick Au layer. On top of this Au layer, 100 nm Al_xN_y thin film was deposited. Finally, 100 nm thick Au layer was deposited and lifted off by conventional photo lithography to form the electrodes of capacitors. All the layers were deposited by radio frequency sputtering at room temperature. Morphology and electro-optical properties for Al_xN_y thin films are now being investigated in the laboratory.

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Nicholas Calvano
Delaware State Univ

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